Abstract Submitted for the MAR07 Meeting of The American Physical Society

Potential profiling of the nanometer-scale charge-depletion layer in $n\text{-}\mathbf{Z}\mathbf{n}\mathbf{O}/p\text{-}\mathbf{N}\mathbf{i}\mathbf{O}$ junction using photoemission spectroscopy YUKIAKI ISHIDA¹, U. of Tokyo, Japan, HIROMICHI OHTA², Nagoya U., Japan, MASAHIRO HIRANO, ERATO-SORST, JST, in Frontier Collaborative Research Center, Tokyo Institute of Technology, Japan, ATSUSHI FUJIMORI, U. of Tokyo, Japan, HIDEO HOSONO³, Frontier Collaborative Research Center, Tokyo Institute of Technology, Japan — We have performed a depth-profile analysis of an all-oxide p-n junction $n\text{-}\mathbf{Z}\mathbf{n}\mathbf{O}/p\text{-}\mathbf{N}\mathbf{i}\mathbf{O}$ [1] using photoemission spectroscopy combined with Ar-ion sputtering, and investigated the potential profile of the space-charge region embedded at the interface [2]. Systematic core-level shifts were observed during the gradual removal of the ZnO overlayer, and were interpreted using a model based on charge conservation. Spatial profile of the potential around the interface was deduced, including the charge-depletion width of 2.3 nm extending on the ZnO side and the built-in potential of 0.54 eV. [1] H. Ohta, et al., APL 83, 1029 (2003). [2] Y. Ishida, et al., APL 89, 153502 (2006).

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Date submitted: 25 Nov 2006 Electronic form version 1.4

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